

Prof. RAKESH KUMAR (Retd)

Dean Faculty of Science (Retd)

Professor & Head Department of Physics (Retd)

Chaudhary Charan Singh University Meerut-250004 (U.P) Cell: 9412705877, 9368210056

Email: <u>drrakeshkumar@hotmail.com</u> <u>profrakeshkumar@gmail.com</u>

**Prof. RAKESH KUMAR (15-01-1958)** 

#### **EDUCATION**

## 1997 - Ph.D (Physics) - Panjab University Chandigarh:

**Thesis:** "Fabrication of Optically Transparent SiN X-ray Mask Membrane with Low Stress and High Radiation Durability by High Temperature LPCVD Deposition"

(<u>Thesis Advisor:</u> Prof. K.N.Pathak, Former Vice Chancellor of Panjab University, Chandigarh

Dr. R.P.Bajpai, Former Chancellor, Vel Tech Rangarajan Dr.Sagunthala R&D Institute of Science and Technology, Avadi, Chennai, Former Vice Chancellor of Guru Jambheshwar University of Science & Technology, Hissar, and Former Vice Chancellor of Kurukshetra University, Kurukshetra).

1981 - M.Sc (Physics) - Panjab University Chandigarh 1978 - B.Sc (Physics) - Panjab University Chandigarh

<u>Academic Specialization</u>: Nanotechnology, Material Science, Semiconductor Device Fabrication, Thin Films, Nano Characterization, Instrumentation

**Thrust Areas of Research:** Surface Plasmon for Photovoltaic and Bio-Sensing Application, **Photonics**, Magneto-Plasmonic Nanostructures for Senor Applications, Nanofabrication and Nanocharacterization

<u>Professional Experience</u>: 37 Years of Experience of Post-Graduate Teaching and Research and administration in university and Industrial Research experience at India and Abroad.

## **Scholarship/Fellowship**

**1987-88** Association for Overseas Technical Scholarship (AOTS), Japan for *Advanced Research in Synchrotron Radiation Lithography for 0.25 μm ULSI Semiconductor Device Fabrication at Research Laboratories of NEC Corporation, Japan* 

## **ACADEMIC APPOINTMENTS**

August 2004-June 2020	Professor of Physics, Chaudhary Charan Singh University, Meerut, India
January 2002-July 2004	Visiting Professor- Laboratorio Tecnologie Avanzate Superfici e Catalisi
	–INFM (CNR), Trieste, Italy.
August 1999-July 2000	Visiting Fellow- NANYANG TECHNOLOGICAL UNIVERSITY, SINGAPORE
June 1995-August 1995	Exchange Visitor- WISCONSIN UNIVERSITY, MADISON, USA

## **Industrial Position Elsewhere:**

Dec 1982-Aug 2001	Research Scientist	CSIR,	India
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## **Visiting Positions Abroad:**

Jan 2002-July 2004	Visiting Professor	Laboratorio Tecnologie Avanzate Superfici e Catalisi -INFM (CNR), Trieste, Italy
Aug 1999-July2000	Visiting Fellow	Nanyang Technological University, Singapore
June 1995-Aug 1995	Exchange Visitor	Wisconsin University Madison, USA
Nov 1990-Jul 1991	Visiting Professor	Institute of Solid State Electronics-CNR, Rome, Italy
Oct 1991-May 1994	Visiting Scientist	OKI Electric Japan
Aug 1988-Aug 1990	Visiting Scientist	NEC Corporation Japan
Aug 1987-July 1988	AOTS Scholarship (Govt of Japan)	NEC Corporation Japan

## Administrative Position (Chaudhary Charan Singh University Meerut, India)

Worked closely with the Vice Chancellor to put the vision of the university into action to discharge following <u>administrative responsibilities</u> in <u>following administrative positions</u>:

2007-2008	Member of Executive Council:
2009-2010	Have been involved in <b>administration</b> as <b>Member of Executive Council</b> of
2011-2014	the university for accreditation and affiliation of colleges with university
2016-2017	and external bodies.
A - 2004 L- 2000	
Aug 2004-Jan 2020	Member of Academic Council

### Sept 2019-Jan 2020: Dean, Faculty of Science

- As a <u>Dean, Faculty of Science</u>, discharged the <u>administrative</u> <u>responsibility</u> of curriculum development, in consultation of Academic Heads of teaching Departments of Faculty to ensure that the University's academic programs are in line with requirement of industry.
- In the capacity of <u>Dean, Faculty of Science</u>, discharged the <u>administrative responsibility</u> of <u>Chairman Board of Study of</u> <u>Faculty</u>.
- In the capacity of <u>Dean, Faculty of Science</u>, discharged the <u>administrative responsibility</u> of <u>Research Degree Committee</u> of <u>Faculty of Science</u>.

Sept 2019-Jan 2020:

As a **Dean, Faculty of Science**, discharged the **administrative** responsibility of (In compliance of University Statute).

- Head, Department of Chemistry
- Head, Department of Toxicology

Sept 2018-Jan 2020: Head, Department of Physics

Sept 2018-Jan 2020: Convener & Member, Board of Studies in Physics

Oct 2010-July 2014 Dean, Faculty of Engineering & Technology

July 2011-July 2014 Head of Department of Physics

July 2011-July 2014 Convener & Member, Board of Studies in subject of Physics

July 2014-Jan 2020 Director, Training & Placement

July 2007-Nov 2011 Director, SC/ST Cell

April 2005-Jan 2006 Chief Proctor- Provide leadership to the nurture discipline and culture in

the campus in the capacity of Chief Proctor of University.

#### **Career Highlight/Achievements**

#### Teaching

#### MoUs formulated for academic and research collaborations:

Memorandum of Understanding (MoU) for Cooperation Agreement on Scientific and Technological Cooperation Marco Polo Cooperation Program between Università degli Studi di Catanzaro Magna Græcia (UMG), Italy and Department of Physics of CCS University Meerut India on 26<sup>th</sup> February 2009 at Meerut, India.

## Research Collaboration with National Institution/Agencies

Name of Institution	Nature of	Contribution done
	Association	
Inter University Accelerator	Research	Development of low energy metallic ion
Center, New Delhi	Collaboration	beams using Electron Cyclotron Resonance
		Ion Source (ECRIS) for various application in
		nanotechnology and material science.

### **Curricula Development**

Academic Programs formulated	Approval of Academic Council	Academic Session
M.Phil in Microelectronics	03/2013	2014-15
Pre Ph.D Course in Physics	03/ 2017	2017-18

- Extensive postgraduate teaching: Physics (Electronics, Solid State Physics, Semiconductor Device Fabrication), Thin Film, Micro and Nanofabrication, Nanostructure Characterization.
- Postgraduate course development for applied and interdisciplinary postgraduate course in physics for M.Sc, M.Phil in Microelectronics and Pre-Ph.D course.

### Post Graduate supervision completed

Level	Students guided	Degree Awarded
M.Phil	16	16
Ph.D	1	1

BAR CODE EVALUTION SYSTEM: Developed bar-code based evaluation of examination answer sheets of

university in 2015, which is used for evaluation of examination answer sheet of students of University and its Affiliated Colleges of various

course (presently this is out sourced from external agency).

Research

**Publications** 

Published Research Papers 52 In Peer Reviewed journals.

Books authored Mathematical Physics, Kedarnath Ramnath Publisher, New Delhi

(2006) ISBN:978-93-80803-

Books edited/chapter: Micro & Nnano fabrication and their Medical Application, pp97,

(Chapter-4) in Bio-MEMS & Biomedical Nanotechnology, Vol.1, Edited by A.P Lee, J. Lee and M. Ferrari, Published by Springer-

Verlog (2006): ISBN 978-0-387-25842-3

## **Patents (International) Granted**

#### 1) US Patent: 7,588,882 B2 (15-9-09)

Method for Fabricating Complex 3-Dimensional Structures on sub-micrometric Scale by Combined Lithography of Two Resist, Inventor: F.Romanato, R.Kumar, E.Di Fabrizio

#### 2) European Patent No: EP 1519227 A8 (12-03-2008)

Procedure for Fabrication of Complex Three Dimensional Structures on Sub-Micron Scale by Means of Two Layers Photoresist Lithographic Process

Inventor: Filippo Romanato, Trieste (IT), Enzo Di Fabrizio, Trieste (IT);

Rakesh Kumar, Chandigarh (IN)

#### **Editorial Board Member of International Journal & Reviewer**

- . Former, Member of Editorial Board: International Journal of Nanolithography
- . Former Member of Editorial Board: International Journal of Applied Nanotechnology
- . Former International Journal of Micro Machining (JMM)-(Institute of Physics)
- . Former Optical Fiber Technology (Elsevier)

## Research projects/Grant Mobilized for Facilities creation during last 10-Years

Funding Agencies	Project	Amount of Grant
		(₹ Lacs)
DST Govt of India	FIST-Level-I	190.00
UGC, New Delhi	Atomic Force Microscope (AFM)	52.00
UGC, New Delhi	Optical Stepper with Nanoimprint Lithography	102.00
University	Class-1000 and Class 10000 Cleanroom facility	40.00
UGC, New Delhi	Scanning Tunneling Microscope (STM)	7.00
UGC, New Delhi	Virtual Laboratory (Lab View and Elvis)	14.00
DST Govt of India	Micro & Nano manipulation Device For Cell and Sub- Cellular Study: Study, realization and experiment on Nano & micro systems for in-situ controlled drug delivery	5.0

Total Grants: 410 Lacs

## **Consultancy/Completed Research Project (Member of Research/Project Team)**

Organization	Project Description
Inter University Accelerator Center, New Delhi	Development of low energy metallic ion beams using Electron Cyclotron Resonance Ion Source (ECRIS) for various application in nanotechnology and material science.
Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy	Gold circular and square pinhole arrays for the European Synchrotron Radiation Facility (ESRF) Troika beam line
Amplipone spa Italy	3D digital scanner based on micro-machined micro-mirror for the metrological measurement of the human ear canal.
Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy	Development of Focused Ion beam (FIB) Lithography technique for fabrication of 2-D array structures for photonic application: Development of 1-D & 2-D Photonic Crystal fabrication technology
Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy	Develop a Multiple-tilt Interface hybrid lithography process as a viable technology to realize 3-D micro and nanostructures embedded with arbitrary shaped and sized patterns:
Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy Ministero dell Istruzione dell	Development of Efficient Fibre-to-waveguide coupling device by designing & fabrication of diffractive optical Elements (DOEs)-Micro lens with continuous relief on-top of optical fibre for fibre-to-waveguide coupling  Lithographic nano patterning of SnO <sub>2</sub> for enhancing gas
Universitae della Ricerca (MIUR), Italy	sensitivity of sensor
Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy	Wavefront Engineering for Diffractive Optics for Optical Trapping:-Development of Optical Tweezers for microparticles manipulation

Ministero dell Istruzione dell Universitae della Ricerca (MIUR), Italy OKI Electric Industry Japan-SORTEC Consortium Japan	Micro & Nano Fabrication by X-ray Lithography for biomedical and other Inter disciplinary applications LPCVD Deposition Process at High Temperature in vertical chamber for deposition of SiN thin film having High Optical Transparency and High Radiation Durability		
CNR-Italy	Fabrication of 1.55 µm gratings for Distributed Feed-back Lasers (DFB) using synchrotron radiation proximity lithography		
NEC Japan-British Petroleum Research	Microwave Deposition of Diamond Thin Film and		
USA	Characterization their application for X-ray mask membrane application		
CSIR Research Laboratory, India	<ul> <li>Worked as member of project-team on project:-</li> <li>"Development of Combine Electron Spectroscopy for Chemical Analysis (ESCA), Auger Electron Spectroscopy (AES) and Ion Scattering System (ISS) System, and</li> <li>X-ray Lithography System Development. Worked as coinvestigator on Design of Electrostatic Lens for Ion Gun and Electron gun and Digital Ion Gauge equipment for measurement of Ultra High Vacuum.</li> </ul>		

# Research Publications in Referred Journals: (930-Reads; Total Citation: 318)

Year	Title	Name of Jurnal	Citation
2009	Nano- A new frontier in present	Advances in Life Science,	8
	century;Bhattacharyya,A.Bhaumik, M.Nandi,	3(1-4), 2009, pp18-23	
	S.Viraktamath, <b>R.Kumar</b> , et.al		
2008	Charge-state distributions of metallic electron	J. Vac. Sci. Technol. A 26,	16
	cyclotron resonance plasmas, P.Kumar, R.Kumar,	97 (2008);	
	G. Rodrigues, P. S. Lakshmy, and D. Kanjilal,		
2008	Local structure, optical and magnetic studies of Ni	J.Phys. Condens Matter	18
	nano structures embedded in a SiO₂ matrix by ion	20 (2008),285211;	
	implantation; S.K.Sharma, P.Kumar, Ravi Kumar,		
	M.Knobel, P.Thakur,K.H.Choi, <u>R.Kumar</u> , et.al		
2006	Development of Zn and Eu beams by plasma	Nucl. Instrum. and	15
	sputtering; P.Kumar, G.Rodrigues, D.Kanjilal,	Meth. B, 246 (2006) 440	
	A.Roy, B.P.Singh, <b>R.Kumar</b> ;		
2006	Development of metallic ion beams using ECRIS;	Nucl. Instrum. and	37
	P.Kumar, G.Rodrigues, P.S.Lakshmy, D.Kanjilal,	Meth. B, 252 (2006) 354	
	B.P.Singh, <u><b>R.Kumar</b></u>		
2005	SnO2 lithographic processing for nano-patterned	Journal of Vacuum	23
	gas sensors	Science & Technology	
		B <b>23</b> , 2784 (2005)	

2005	Three-dimensional digital scanner based on	J.Vac.Sci. Technol. B 23	23
	micro machined micro mirror for the metrological	(2005), 2990	
	measurement of the human ear canal;		
	M.Prasciolu, R.Malureanu, S.Cabrini, D.Cojoc,		
	L.Businaro, A.Carpentiero, R.Kumar, E.Di Fabrizio;		
2005	Low Cost Transparent SU-8 Membrane Mask for	MicrosystemTechnologi	8
	Deep X-ray lithography, S.Cabrini, F.Perennes,	es Vol.11 (2005), 372	
	B.Marmiroli, A.Olivo, A. Carpentiero, R.Kumar,		
	et.al,		
2005	Focused Ion Beam Lithography for Two	Microelectronic	67
	Dimensional Array Structures for Photonic	Engineering <i>Vol.</i> 78–79	
	Applications; S.Cabrini, A. Carpentiero, R.Kumar,	(2005), 11	
2005	et.al,		
2005	SnO <sub>2</sub> Lithographic Processing for Nano-patterned	J.Vac.Sci.& Technol.	23
	Gas Sensors, SnO <sub>2</sub> Lithographic Processing for	B23(6) (2005),2784	
	Nano-patterned Gas Sensors, P.Candelro,		
	E.Comini, C.Baratto, G.Faglia, S.Sberveglieri,		
2004	R.Kumar, et.al  Fabrication through silicon micro machining of 3D	Modi 9 Pio Eng Vol 6 /	6
2004	scanner for optical determination of the ear	Medi. & Bio. Eng. Vol 6 (	O
	canal; M.Prasciolu, S.Cabrini,	2004) (Print ISSN:1727-	
	D.Cojoc,R.Malureanu, <u>R.Kumar, et.al</u>	1983)	
2004	Interface lithography: A hybrid litho-graphic	Nanotechnology	10
2004	approach for the fabrication of Patterns	Vol.16(1) (2004), 40,	10
	embedded in 3-D structures: F. Romanato,	Vol.10(1) (2004), 40,	
	R.Kumar, et.al		
2004	X-ray lithography for micro- and nano-fabrication	J.Phys. Condensed	34
	at ELETTRA for inter-disciplinary applications	Matter Vol. 16	
	(Invited), E.Di Fabrizio, R.Fillipo,F.Perenneas,	(2004),\$3517	
	S.Cabrini, <b>R.Kumar</b> , et.al	(200 1))33317	
2004	Design and Implementation of Optical Tweezer	SPIE Vol.5477 (2004),281	7
	Arrays using Diffractive Optical Elements,		
	D.Cojoc, E.Ferrari, S.Cabrini, R.Malureanu,		
	Miltcho B.Danailov, A.Carpentiro, M.Prasciolu,		
	R.Kumar, et.al		
2004	Design and Fabrication of Diffractive Optical	Jap. J. Appl. Physics	10
	Element-Microlens with Continuous Relief	Vol.43 (2004), 3772	
	Fabricated On-Top of Optical Fibre by Focused Ion		
	Beam for Fibre-to-Waveguide Coupling,		
	F.Shiappelli, <u><b>R.Kumar,</b></u> et.al		
2004	Electromagnetically actuated surface micro-	Jap. J. Appl. Physics,	6
	machined free standing torsion beam micro-	ol.43 (2004), 418;	
	mirror made by electroplated nickel, M.Prasciolu,		
	A.Carpentiro, <b>R.Kumar, et.al</b>		

2004	Efficient fiber-to-waveguide coupling by a lens on the end of the optical fiber fabricated by focused ion beam milling, F.Shiappelli, R.Kumar, et.al,	Microelectronic Engineering, Vol. 73–74 (2004), 39;	85
2003	X-ray lithography patterning of magnetic materials and their characterization, P.Candelor, R.Kumar, et.al	Jap. J. Applied Physics, Vol. 42 (2003), 3802.	4
2003	Design and fabrication of on-fiber diffractive elements for fiber-waveguide coupling by means of e-beam lithography, M.Prasciolu, D.Cojoc, S.Cabrini, L.Businaro, P.Candeloro, M.Tormen, R.Kumar, et.al	Microelectronic Engineering, Vol. 67–68, (2003) 169;	30
2003	Fabrication of diffractive optical elements on- fiber for photonic applications by Nanolithography, M.Prasciolu, P.Candeloro, R.Kumar, et.al	Jap. J. Applied Physics. Vol. 42 (2003), 4177	12
1994	Fabrication of reliable x-ray mask using high- temperature deposited SiN membrane by low- pressure chemical vapour deposition system,T.Ohta, R.Kumar, et.al	SPIE 2254(1994) 304,	7
1994	High temperature deposition of SiN films using low pressure chemical vapor deposition system for x-ray mask application, T.Ohta, R.Kumar, Y.Yamashita, H.Hoga,	J.Vac.Sci. Technol. B12 (1994),585	12
1993	Improvement in Radiation Stability of SiN X-Ray Mask Membranes, T.Arakawa, H.Okuyama, Y.Tamashita, T. Ohta, R.Kumar, S.Noda, H.Hoga,	Jpn. J. Appl. Phys. 32 (1993), 5941	11
1992	CD control of sub-200 nm x-ray masks using an e- beam writer, E.Di Fabrizio, L.Luciani, M.Baciocchi, L.Mastergiacomo, R.Kumar, et.al	Microelectronic Engineering, Vol. 17 (1992) 171	2
1992	Fabrication of DFB laser gratings using synchrotron radiation proximity Lithography.  M.Gentili, L.Grella, M.Baciocchi, R.Kumar, et.al	Microelectronic Engineering, Vol. 17 (1992) 551.	2
1992	Optically High Transparent SiN Mask Membrane with Low Stress Deposited by Low Pressure Chemical Vapor Deposition, R.Kumar, et.al	Jpn. J. Appl. Phys. 31 (1992), 4195.	13
1991	0.1μmX-raymaskreplication,M.Gentili,R.Kumar,et.al	J. Vac. Sci. Technol. B9 (1991), 3319.	12
1991	Thermal stability improvement in novolak based resist by synchrotron radiation hardening process, R.Kumar, K.Fuji;	J. Vac. Sci. Technol. B 9 (1991) 2523;	1
1991	X-ray irradiation effects on a microwave - plasma chemical vapor deposition diamond membrane, K. Suzuki, R.Kumar, et.al	J. Vac. Sci. Technol. B 9, 3266 (1991);	20

**Conference (International)** 

	Conference (International)				
Year	Title of Conference	Title Subject of Presentation			
16-18	2 <sup>nd</sup> International Conference on	Interface lithography: Hybrid approach			
March	Nanoscience & Technology (INCOSAT-	for fabrication of wave guide pattern			
2006	2006),	embedded in 3-D photonic crystal			
		structure: Kaushal Rani, <u>R.Kumar</u> , Beer			
		Pal Sing			
Nov 8-	, .	SiN Film Deposition by High			
10,	Physics, IIT Kanpur (India), Nov 8-10	Temperature LPCVD: R.Kumar			
1995	<b>(1995),</b> pp 73				
	7 <sup>th</sup> International Workshop on Physics	Selective Tungsten Deposition using			
	of Semiconductor Device-	Resist Stencil Mask, <b>R. Kumar</b> , pp 161			
	1991( <i>IWPSD-91</i> ),				
	2-5 Dec 1991 New Delhi India				
31 <sup>st</sup>	49 <sup>th</sup> International Electron, Photon &	3-D Digital Scanner based on micro			
May-3 <sup>rd</sup>	Ion Beam Conference , 2005 (EPIBN-	machined micro-mirror for the			
June	2005), Orlando, USA	metrological measurement of the			
2005		human ear canal based on MOMS			
		scanning micro mirror: M.Prasciolu,			
		R.Malureanu, S.Cabrini, D.Cojac,			
		R.Kumar, E.DiFabrizio			
31 <sup>st</sup>	49 <sup>th</sup> International Electron, Photon &	SnO <sub>2</sub> lithographic processing for nano-			
May-	Ion Beam (EPIBN-2005) Conference ,	patterned gas sensor::P.Candeloro,			
3 <sup>rd</sup>	2005, <b>,Orlando, USA</b>	E.Comini, C.Baratto, G.Faglia,			
June		G.Sberveglieri, R. Kumar, A.			
2005	D 1: (1) 2011 1 1 1 1	Carpentiero and E. Di Fabrizio			
19-22	Proceedings of the 30th International	Focused ion beam lithography for two			
Sept	Conference on Micro- and Nano-	dimensional array structures for			
2004	Engineering,2004, Rotterdam	photonic applications; <b>S. Cabrini</b> , A.			
10.33	(Holland)	Carpentiero, R. Kumar, et.al			
19-22	30 <sup>th</sup> International Micro and Nano	3-D Digital Scanner based on micro			
Sept	Engineering (MNE-04) Conference	machined micro-mirror for the			
2004,	2004  Rottordom (Holland)	metrological measurement of the			
	Rotterdam (Holland)	human ear canal based on scanning			
		micromirror:M.Prasciolu,R.Malureanu,			
		S.Cabrini, D.Cojac, <u>R.Kumar,</u>			
31 <sup>st</sup>	10 <sup>th</sup> Mediterranean Conference on	E.DiFabrizio			
July-5 <sup>th</sup>		Fabrication through silicon micromachining of 3-D scanner for			
_	Medical and Biological Engineering				
August	(MEDICON), 2004 Ischia, Italy	optical determination of ear canal:			
2004,		M.Prasciolu, S.Cabrini,D.Cojoc,			
		R.Malureanu, <b>R.Kumar,</b> et.al			

June	6 <sup>th</sup> SPIE International Conference on	Design and implementation of optical
2004	Correlation Optics, SPIE, Bellingham, WA, 2004	tweezer arrays using diffractive optical elements: Dan Cojoc; Enrico Ferrari; Stefano Cabrini; Radu Malureanu; Miltcho B. Danailov; Alessandro Carpentiero; Mauro Prasciolu; Rakesh Kumar; et.al
22–25	Proceedings of the 29 <sup>th</sup> international	Efficient fibre-to-waveguide coupling by
Sept	conference on Micro and Nano	a lens on the end of the optical fibre
2003	Engineering 2003, Cambridge, UK	fabricated by focused ion beam milling:
20.24	2003	F.Schiappelli, R.Kumar, et.al
28-31 Octobe	Digest of Papers of International Conference on Micro processes &	Design & Fabrication of DoE-microlense with continuous relief fabrication on-
r 2003	Nanotechnology 2003, <b>Tokyo, Japan</b>	top of optical fibre by Focused Ion
1 2003	Nanoteenhology 2003, Tokyo, Japan	Beam for Fibre to Waveguide coupling:
		F. Schiappelli, <b>R.Kumar</b> , et.al
6-8 Nov	Digest of Papers of International	Fabrication of diffractive optical
2002	Conference on Micro processes &	elements for photonic applications by
	Nanotechnology 2002,	nanolithography: E.Di Fabrizio,
	6-8 Nov. 2002, Tokyo, Japan	M.Prasciolu, <b>R.<u>Kumar</u></b> , et.al
6-8	International Conference on Micro	X-ray lithography patterning of
Nov.	processes & Nanotechnology 2002,	magnetic material and their
2002	Tokyo, Japan	<b>characterization:</b> E. <u>Di Fabrizio,</u> P. <u>Candeloro, <b>R.Kumar</b>,</u> et.al
Sept.	Proceedings of the 28th International	Design and fabrication of on-fiber
16-19,	Conference on Micro- and Nano-	diffractive elements for fiber-wave
2002	Engineering,2002, , Lugano, Switzerland	guide coupling by means of e-beam lithography:
		M.Prasciolu, D.Cojoc, S.Cabrini, L.Busin
		aro, P.Candeloro, M.
22.24	SPIE International Symposium on	Tormen, R.Kumar, et.al
22-24 April	SPIE International Symposium on Photomask and X-Ray Mask	Fabrication of reliable x-ray mask using high-temperature deposited SiN
1994	Technology 1994, <b>Kawasaki, Japan</b> .	membrane by low-pressure chemical
1334	reemology 1994, <b>Rawasaki, Japan</b> .	vapour deposition system: T.Ohta,
		R.Kumar, et.al
March	54th Meeting of Japan Society of	Optical Properties of LPCVD Deposited
1993	Applied Physics Meeting, 29-a-L-7 (1993).	SiN Membrane: T.Ohta, R.Kumar, et.al
12.15	Eth	Improvement in Radiation Stability of
13-16	5 <sup>th</sup> International MicroProcess	SiN X-Ray Mask Membranes:
July,	Conference, 1992, Kawasaki, Japan	T.Arakawa, H.Okuyama, Y.Yamashita,
1992	Eth Latauri Lati	T.Ohta, R.Kumar, S. Noda & H.Hoga
July 13-	5 <sup>th</sup> International Micro Process	Optically High Transparent SiN Mask
16		
16, 1992	Conference (1992), , Kawasaki, Japan	Membrane with Low Stress Deposited by Low Pressure Chemical Vapor

March	54 <sup>th</sup> Meeting of Japanese Society of	Improvement in Synchrotron radiation	
1993	Applied Physics Meeting, 29-a-L-10	(SR) durability of X-ray mask	
1555	(1993).	Membrane: T.Ohta, <u>R.Kumar</u> , et.al	
August		<del></del>	
August	Japan Society of Applied Physics 53 <sup>rd</sup>	LPCVD Deposited X-Ray mask	
1992	Autumn Meeting 1992.	Membrane: T.Ohta, <u><b>R.Kumar</b></u> , et,al	
29-31 <sup>st</sup>	35 <sup>th</sup> International Electron, Photon &	X-ray Irradiation effects in Microwave	
May',	Ion Beam (EPIBN) Conference , 1991	Plasma CVD deposited diamond	
1991	(Annual International conference);	membrane: K.Suzuki, <b>R.Kumar</b> , et.al	
	Seattle, USA		
Sept	Proceedings of the International	CD control of sub-200 nm X-ray masks	
1991	Conference Micro Engineering 91,,	using an E-beam writer:E.Di Fabrizio,	
	Rome, Italy	L.Luciani, <u>M.Baciocchi</u> ,	
		L.Mastrogiacomo, <b>R.Kumar</b> , L.Scopa	
Sept	Proceedings of the International	Fabrication of DFB laser gratings using	
1991	Conference Micro Engineering 91,	synchrotron radiation proximity	
	Rome, Italy	lithography: M.Gentili, L.Grella,	
		M.Baciocchi, <b>R.Kumar</b> , et.al	
29-31 <sup>st</sup>	35 <sup>th</sup> International Electron, Photon &	0.1 m X-ray Mask Replication:	
May'	Ion Beam (EPIBN) Conference , 1991	M.Gentili, <b>R.Kumar</b> , et.al	
1991	(Annual International conference)		
	Seattle, USA		
March-	Japan Society of Applied Physics 49 <sup>th</sup>	Atmospheric exposure effects on resist	
1988	Spring Meeting, 1988.Japan	sensitivity: R.Kumar, K.Fujii, K.Okada:	
March-	Japan Society of Applied Physics 49 <sup>th</sup>	Characterization of TSNE Resist-A	
1988	Spring Meeting, 1988.Japan	Silicon Containing Resist for X-ray	
		Lithography: R.Kumar; et.al	